

TERBIUM

Sputtering Target

NS6130-10-1547

Quick Facts

Product	:	Terbium Sputtering Target
Stock No	:	NS6130-10-1547
CAS	:	7440-27-9
Molecular Formula	:	Tb
Form	:	Solid

Technical Specification

Molecular Weight	Diameter	Thickness
158.93 g/mol	50.8mm	3mm

A terbium sputtering target is used in advanced manufacturing and research to deposit thin films for electronic, magnetic, and optical applications. It enhances magnetic storage devices, creates optical coatings for lenses, and fabricates sensors. The sputtering process involves bombarding the target with high-energy particles, ejecting terbium atoms to form uniform films. It's crucial in developing new technologies in materials science and electronics.

Applications:

- Thin Film Deposition
- Magnetic Storage
- Optical Coatings
- Sensors
- Research

